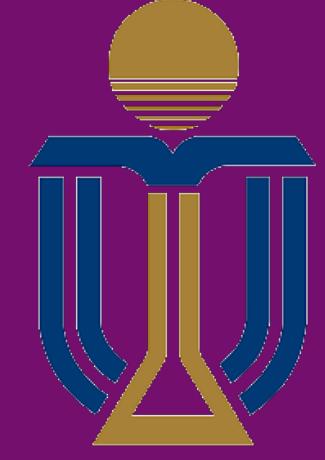




# EMOGen: Enhancing Mask Optimization via Pattern Generation

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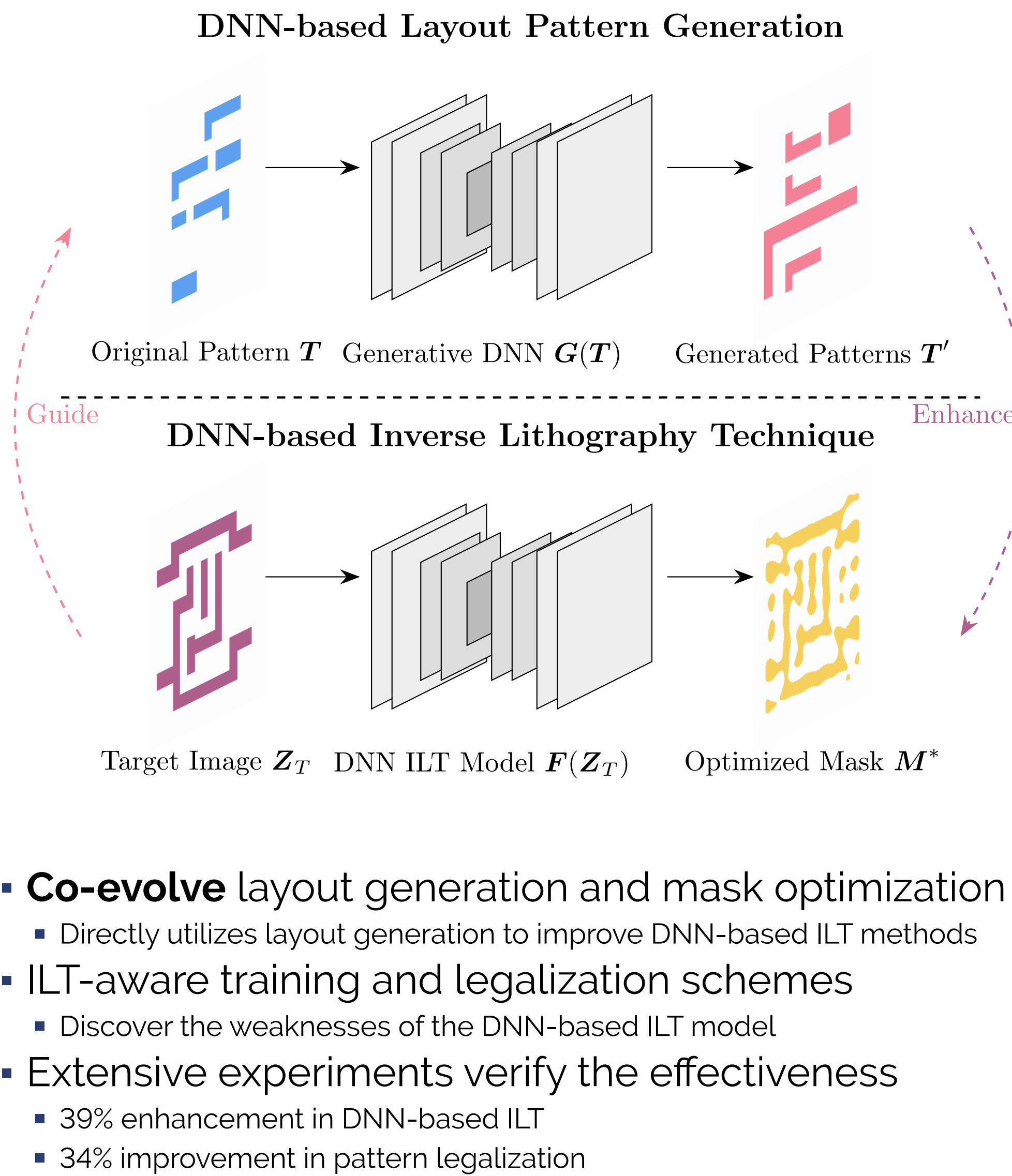


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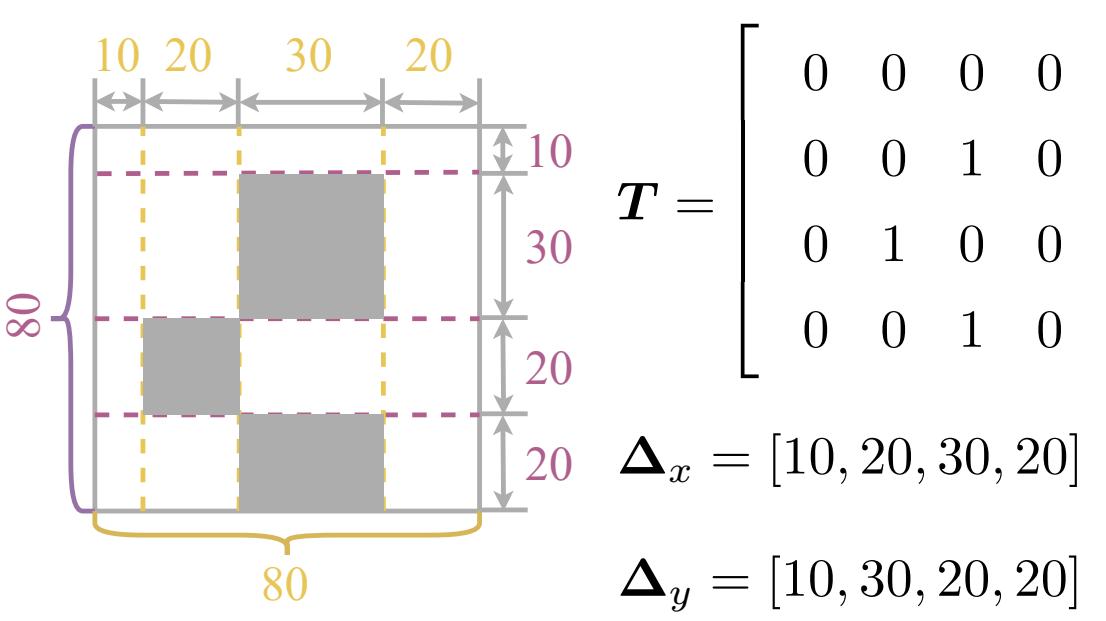
<sup>3</sup>Hong Kong Baptist University

## Motivation



## Preliminaries

- Squish Pattern: efficiently represents layout patterns
  - A topology matrix + two geometry vectors

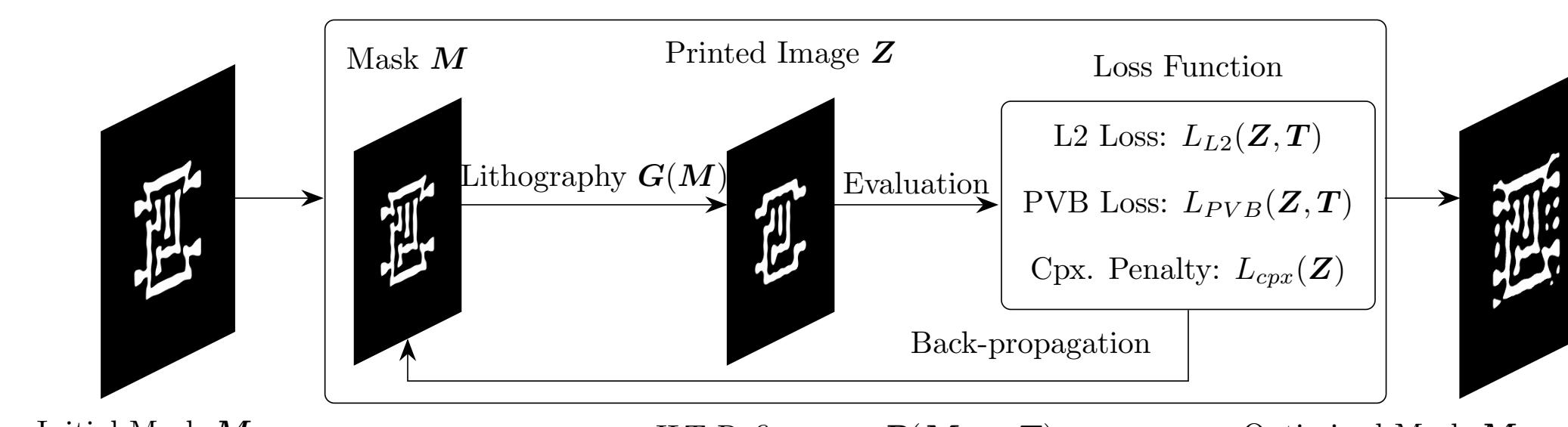


- Layout Pattern Generation: autoencoder-based

$$T' = f_{dec}(f_{enc}(T) + \epsilon\mathcal{N}(0, I)). \quad (1)$$

- Map the topology matrices to a latent space
- Generate new patterns by perturbing latent features

- ILT for Mask Optimization



- Lithography simulation:
  $I = H(M) = \sum_{k=1}^K \mu_k |h_k \otimes M|^2$

- Objectives:
  $L2(\mathbf{Z}_{nom}, \mathbf{Z}_T) = \|\mathbf{Z}_{nom} - \mathbf{Z}_T\|^2$ 
 $PVB(\mathbf{Z}_{max}, \mathbf{Z}_{min}) = \|\mathbf{Z}_{max} - \mathbf{Z}_{min}\|^2$

- Metrics: L2, PVB, EPE (edge placement error)

## Formulation

- Mask optimization problem

$$\mathbf{M}^* = f_M(\mathbf{Z}_T | \theta_M). \quad (2)$$

- $\mathbf{Z}_T$  is the target image.
- $\mathbf{M}^*$  represents the optimized masks given by the ILT model.

- Pattern generation problem

$$\mathbf{T}', \Delta'_x, \Delta'_y = f_P(\mathbf{T}, \Delta_x, \Delta_y | \theta_P). \quad (3)$$

- $f_P(\cdot)$  denotes the pattern generation model with the parameters  $\theta_P$ .
- $\mathbf{T}', \Delta'_x, \Delta'_y$  represent the generated topology and geometry.

- Co-optimization problem → two players competing with each other

$$\min_{\theta_M} \max_{\theta_P} L_{ILT}(f_M(\mathbf{X} | \theta_M), \mathbf{X}) \text{ s.t. } \mathbf{X} = r(f_P(\mathbf{T}, \Delta_x, \Delta_y | \theta_P)). \quad (4)$$

- $L_{ILT}$  is the loss function of ILT.
- $r(\cdot)$  converts the generated pattern to ILT input.

- Legalization of the generated patterns

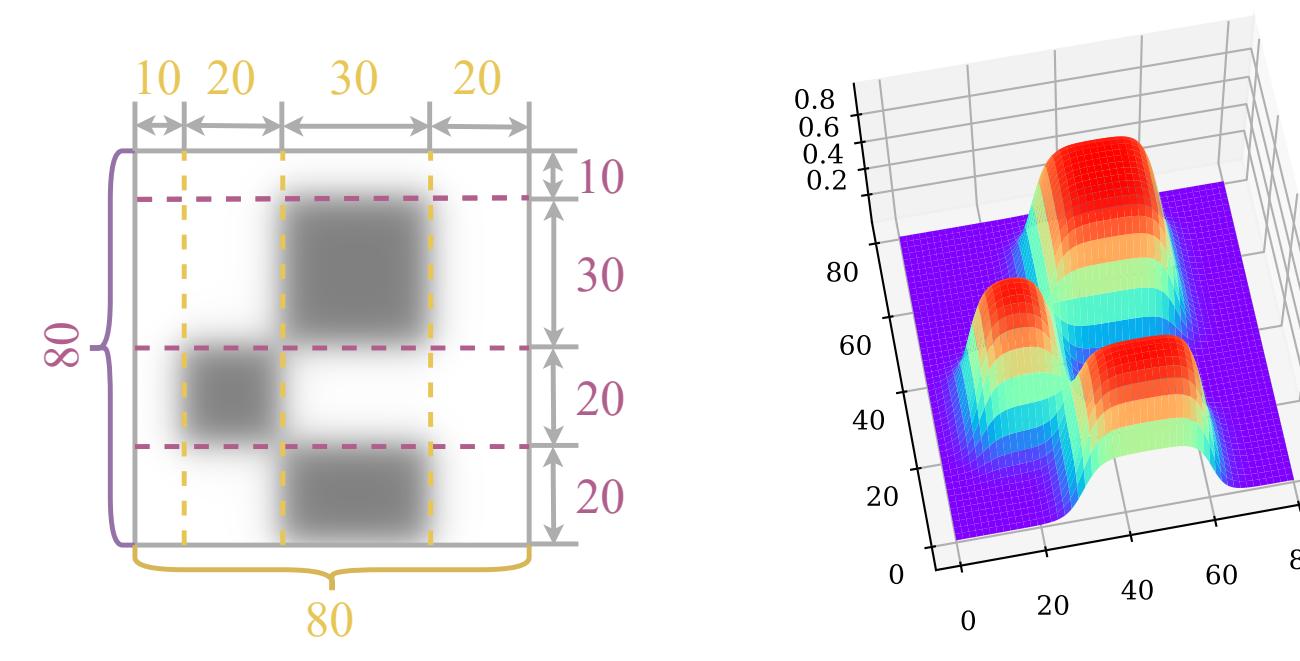
$$\sum_{k \in \mathbf{k}_x} \Delta'_{x,k} \geq \text{Space}_{\min}, \sum_{k \in \mathbf{k}_y} \Delta'_{y,k} \geq \text{Space}_{\min}, \forall k_x, k_y \in \mathbf{S}_{\min}, \quad (5)$$

$$\sum_{l \in \mathbf{l}_x} \Delta'_{x,l} \geq \text{Width}_{\min}, \sum_{l \in \mathbf{l}_y} \Delta'_{y,l} \geq \text{Width}_{\min}, \forall l_x, l_y \in \mathbf{W}_{\min}, \quad (6)$$

$$\sum_{(i,j) \in \mathbf{p}} \Delta'_{x,i} \Delta'_{y,j} \in [\text{Area}_{\min}, \text{Area}_{\max}], \forall \text{ polygon } \mathbf{p}. \quad (7)$$

## Training

- Make it differentiable with  $r(\cdot)$ , the bell-shape function



## Step 1: Pattern Generation Optimization

DNN-based Pattern Generation

Pattern  $Z_0$  Squish Patterns DNN  $f_P(T, \Delta_x, \Delta_y | \theta_P)$

New Patterns Target Image  $Z_T$

Update

## Step 2: ILT Optimization

DNN-based ILT

DNN  $f_M(Z_T | \theta_M)$

Optimized Mask  $M^*$

Update

Step 1 Pattern Generation

$L_{Gen} = KL_T + KL_A - L_{ILT}$

$\theta_P = \theta_M - \frac{\partial L_{Gen}}{\partial \theta_P}$

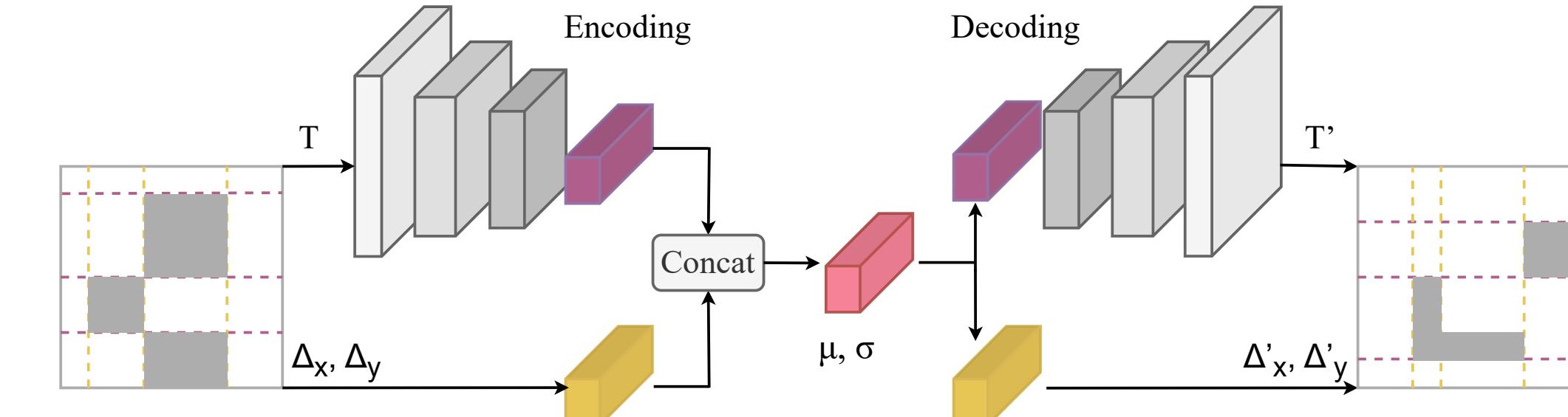
Step 2 ILT

$L_{ILT} = L2 + PVB$

$\theta_M = \theta_M - \frac{\partial L_{ILT}}{\partial \theta_M}$

## Models

- Pattern Generation Model



- Mask Optimization Models

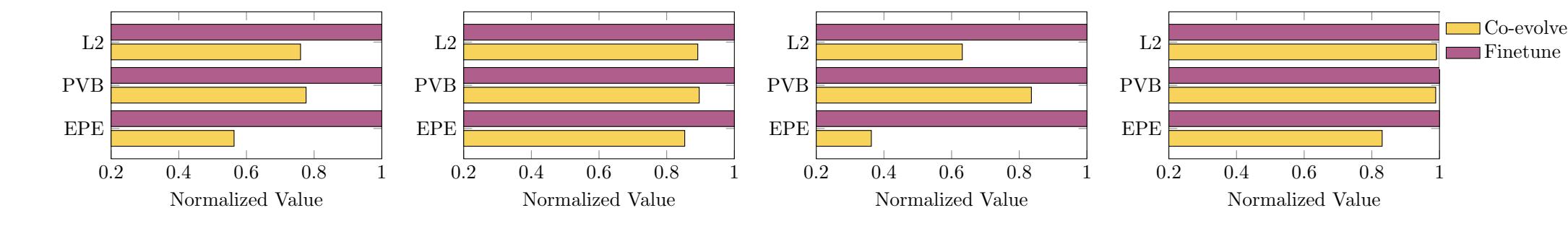
- **GAN-OPC** It follows the design of generative adversarial network (GAN).
- **Neural-ILT** A UNet is utilized in Neural-ILT to predict the optimized mask.
- **DAMO** It improves the GAN for ILT with the backbone based on UNet++ and a multiscale discriminator.
- **CFNO** Combining the basic principles of Vision Transformer (ViT) and Fourier Neural Operator (FNO).

- Codebase from OpenILT and LithoBench
  - <https://github.com/OpenOPC/OpenILT>
  - <https://github.com/shelljane/LithoBench>

## Experiments

- Comparison Between ILT Models With and Without Co-evolution

Method	GAN-OPC		NeuralILT		DAMO		CFNO		Ratio	
	Setting	Finetune	Co-evolve	Setting	Finetune	Co-evolve	Setting	Finetune	Co-evolve	
L2	50.388	38.288	50.804	45.313	53.448	33.757	46.280	45.863	100	0.81
PVB	69.549	53.987	61.464	55.082	65.447	54.703	62.514	61.811	100	0.87
EPE	7.1	4.0	7.5	6.4	10.2	3.7	5.9	4.9	100	0.61



- Comparison on the Legalization of Generated Patterns

Metric	$\mu_V$	L2	PVB	EPE
No legalization	0.094	51777	57149	22.0
Design Rules Only	0.070	50782	57335	21.4
Design Rules + ILT (ours)	<b>0.062</b>	<b>64800</b>	<b>65394</b>	<b>44.1</b>